

ABSTRACT OF THE DISCLOSURE

A charged-particle beam writer which draws
a pattern on a specimen with a charged-particle beam
generated from a single particle generator by both of
5 a VSB strategy and a scan-projection strategy, the
charged-particle beam writer comprising a data creating
unit configured to create pattern data representing
a state where a first-type figure drawn by the VSB
strategy and a second-type figure drawn by the scan-
10 projection strategy are arranged on the specimen,
a computing unit configured to calculate, on the basis
of the pattern data, the amount of correction for
correcting the drawing dimensions of the first-type
figure on the specimen and the drawing dimensions of
15 the second-type figure on the specimen, and a control
unit configured to control the dose of beam at each
position on the specimen on the basis of the calculated
amount of correction.